Author(s)	Book chapter title	Chapter, pages	Book title	Editors	Publisher	Year published	DOI or weblink
Sitter, Helmut; Faschinger, Wolfgang	Atomic Layer Epitaxy of II-VI Compound Semiconductors	Ch. 12, pp. 219-237	Festkörperprobleme (vol. 30)	Rössler, Ulrich	Springer, Berlin	1990	https://doi.org/10.1007/BFb0108278
Leskelä, M.; Niinistö, L.	Chemical aspects of the ALE process	Ch. 1, pp. 1-39	Atomic layer epitaxy	Suntola, T.; Simpson, M.	Blackie and Son, London	1990	https://link.springer.com/book/9789401066617
Pakkanen, T.	Theoretical aspects of the ALE process	Ch. 2, pp. 40-62	Atomic layer epitaxy	Suntola, T.; Simpson, M.	Blackie and Son, London	1990	https://link.springer.com/book/9789401066617
Mason, N. J.	Theoretical aspects of the ALE growth mechanism	Ch. 3, pp. 63-109	Atomic layer epitaxy	Suntola, T.; Simpson, M.	Blackie and Son, London	1990	https://link.springer.com/book/9789401066617
Tischler, M. A.; Bedair, S. M.	Comparison of ALE with other techniques	Ch. 4, pp. 110-154	Atomic layer epitaxy	Suntola, T.; Simpson, M.	Blackie and Son, London	1990	https://link.springer.com/book/9789401066617
Yao, T.	Atomic layer epitaxy of III-V compounds	Ch. 5, pp. 155-180	Atomic layer epitaxy	Suntola, T.; Simpson, M.	Blackie and Son, London	1990	https://link.springer.com/book/9789401066617
Suntola, Tuomo	Atomic layer epitaxy	pp. 601-663	Handbook of Crystal Growth (1st ed., vol. 3)		Elsevier	1994	
Malygin, A.; Malkov, A.; Dubrovenskii, S.	The chemical basis of surface modification technology of silica and alumina by molecular layering method	Ch. 1.8, pp. 213-236	Adsorption on new and modified inorganic sorbents (Studies in Surface Science and Catalysis, vol. 99)	Dabrowski, A.; Tertykh, V. A.	Elsevier	1996	https://doi.org/10.1016/S0167-2991(06)81022-0
Haukka, Suvi; Lakomaa, Eeva-Liisa; Suntola, Tuomo	Adsorption controlled prepartion of hererogeneous catalysts	pp. 715-750	Adsorption and its Applications in Industry and Environmental Protection (Studies in Surface Science and Catalysis, vol. 120 part A)	Dabrowski, A.	Elsevier	1998	https://doi.org/10.1016/S0167-2991(99)80570-9
Ritala, Mikko; Leskelä, Markku	Atomic layer deposition	Ch. 2, pp. 103-159	Handbook of Thin Films Materials (vol. 1)	Nalwa, H. S.	Academic	2002	https://www.elsevier.com/books/handbook-of-thin-films-five-volume-set/nalwa/978-0-12-512908-4
Ritala, Mikko	Atomic Layer Deposition	Ch. 2.1., pp. 17-64	High-k Gate Dielectrics	Houssa, Michel	Taylor & Francis	2004	https://www.taylorfrancis.com/books/edit/10.1201/9781420034141/high-gate-dielectrics-michel-houssa
Päiväsaari, Jani; Niinistö, Jaakko; Myllymäki, Pia; Dezelah, Chuck; Winter, Charles H.; Putkonen, Matti; Nieminen, Minna; Niinistö, Lauri	Atomic layer deposition of rare earth oxides	Ch. 2, pp. 15-32	Rare earth oxide thin films: Growth, characterization, and applications (Topics in Applied Physics, vol 106)	Fanciulli, Marco; Scarel, Giovanna	Springer	2007	https://link.springer.com/chapter/10.1007/11499893_2
Seidel, Thomas E	Atomic Layer Deposition	Ch. 14, 35 pp.	Handbook of Semiconductor Manufacturing Technology (2nd ed)	Nishi, Yoshio; Doering, Robert	CRC Press	2008	https://doi.org/10.1201/9781420017663
Ritala, Mikko; Niinistö, Jaakko	Atomic Layer Deposition	Ch. 4, pp. 158-206	Chemical Vapour Deposition:Precursors, Processes and Applications	Jones, Anthony C.; Hitchman, Michael L.	RSC Publishing	2009	https://pubs.rsc.org/en/content/ebook/978-0-85404-465-8
Pakkala, Arto; Putkonen, Matti	Atomic layer deposition	Ch. 8, pp. 364-391	Handbook of Deposition Technologies for Films and Coatings (3rd ed.)	Martin, P.	William Andrew, New York	2010	https://www.elsevier.com/books/handbook-of-deposition-technologies-for-films-and-coatings/martin/978-0-8155-2031-3
Puurunen, Riikka; Kattelus, Hannu; Suntola, Tuomo	Atomic layer deposition in MEMS technology	Ch. 26, pp. 433-446	Handbook of Silicon Based MEMS Technologies and Materials		William Andrew	2010	https://dx.doi.org/10.1016/B978-0-8155-1594-4.00026-7
Musgrave, Charles	Theoretical modeling of ALD processes	Ch. 1, pp. 1-21	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch1
Panda, Sovan Kumar; Shin, Hyungjung	Step coverage in ALD	Ch. 2, pp. 23-40	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch2
Putkonen, Matti	Precursors for ALD processes	Ch. 3, pp. 41-59	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch3
Clavel, Guylhaine; Marichy, Catherine; Pinna, Nicola	Sol-Gel Chemistry and Atomic Layer Deposition	Ch. 4, pp. 61-82	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch4
George, Steven; Yoon, Byunghoon; Hall, Robert; Abdulagatov, Aziz; Gibbs, Zachary; Lee, Yonghee; Seghete, Dragos; Lee, Byoung	Molecular Layer Deposition of Hybrid Organic-Inorganic Films	Ch. 5, pp. 83-107	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch5
Meyer, Jens; Riedl, Thomas	Low-Temperature Atomic Layer Deposition	Ch. 6, pp. 109-130	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch6
Kessels, Erwin; Profijt, Harald; Potts, Stephen; van de Sanden, Richard	Plasma Atomic Layer Deposition	Ch. 7, pp. 131-157	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch7
Hwang, Cheol Seong	Atomic Layer Deposition for Microelectronic Applications	Ch. 8, pp. 159-192	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch8
Lee, Han-Bo-Ram,; Bent, Stacey	Nanopattering by Area-Selective Atomic Layer Deposition	Ch. 9, pp. 193-225	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch9

Elam, Jeffrey	Coatings on High Aspect Ratio Structures	Ch. 10, pp. 227-249	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch10
Fan, Hong Jin; Nielsch, Kornelius	Coatings of Nanoparticles and Nanowires	Ch. 11, pp. 251-270	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch11
Parsons, Gregory N	Atomic Layer Deposition on Soft Materials	Ch. 12, pp. 271-300	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch12
Knez, Mato	Application of ALD to Biomaterials and Biocompatible Coatings	Ch. 13, pp. 301-325	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch13
Marichy, Catherine; Pucci, Andrea; Willinger, Marc-Georg; Pinna, Nicola	Coatings of Carbon Nanotubes	Ch. 14, pp. 327-343	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch14
Gaillot, Davy; Summers, Christopher	Inverse Opal Photonics	Ch. 15, pp. 345-376	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch15
Szeghalmi, Adriana V; Knez, Mato	Nanolaminates	Ch. 16, pp. 377-399	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch16
Leskelä, Markku	Challenges in Atomic Layer Deposition	Ch. 17, pp. 401-421	Atomic Layer Deposition of Nanostructured Materials	Pinna, N.; Knez, M.	Wiley-VCH	2011	https://doi.org/10.1002/9783527639915.ch17
Winter, Charles H; Knisley, Thomas J; Kalutarage, Lakmal C; Zavada, Mark A; Klesko, Joseph P; Perera, T Hiran	Metallic Materials Deposition: Metal-Organic Precursors		Encyclopedia of Inorganic and Bioinorganic Chemistry (2nd ed)		John Wiley and Sons	2012	https://dx.doi.org/10.1002/9781119951438.eibc0128.pub2
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Fundamentals of Atomic Layer Deposition	Ch. 1, pp. 1-31	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch1
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Elemental Semiconductor Epitaxial Films	Ch. 2, pp. 33-49	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch2
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	III-V Semiconductor Films	Ch. 3, pp. 51-66	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch3
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Oxide Films	Ch. 4, pp. 67-159	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch4
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Nitrides and Other Compounds	Ch. 5, pp. 161-182	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch5
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Metals	Ch. 6, pp. 183-206	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch6
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	Organic and Hybrid Materials	Ch. 7, pp. 207-213	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch7
Kääriäinen, Tommi; Cameron, David; Kääriäinen, Marja-Leena; Sherman, Arthur	ALD Applications and Industry	Ch. 8, pp. 214-242	Atomic Layer Deposition: Principles, Characteristics, and Nanotechnology Applications, Second Edition		Scrivener Publishing LLC.	2013	https://onlinelibrary.wiley.com/doi/10.1002/9781118747407.ch8
Knoops, Harm; Potts, Stephen; Bol, Ageeth; Kessels, Erwin	Atomic layer deposition	Ch. 27, pp. 1101-1134	Handbook of Crystal Growth (3rd ed., vol. 3)	Kuech, Thomas	Elsevier	2014	https://www.sciencedirect.com/science/article/pii/B9780444633040000275
He, Wei	ALD: Atomic layer deposition - Precise and conformal coating for better performance	Ch. 82, pp. 2959-2996	Handbook of Manufacturing Engineering and Technology (vol. 6)	Nee, A.	Springer	2014	https://doi.org/10.1007/978-1-4471-4670-4_80
Leskelä, Markku; Niinistö, Jaakko; Ritala, Mikko	Atomic Layer Deposition	Ch. 4.05, pp. 101-123	Comprehensive Materials Processing (vol. 4)	Hashmi, S.; Cameron, D.	Elsevier	2014	https://www.sciencedirect.com/science/article/pii/B9780080965321004015
Dendooven, Jolien	Atomic Layer Deposition in Nanoporous Catalyst Materials	Ch. 7, pp. 167-197	Atomically-Precise Methods for Synthesis of Solid Catalysts (RSC Catalysis series No. 22)	Hermans, Sophie; de Bocarme, Thierry Visart	Royal Society of Chemistry	2014	https://doi.org/10.1039/9781782628439-00167
Gordon, Roy G.	ALD Precurorsors and Reaction Mechanisms	Ch. 2, pp. 15-46	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Elliot, Simon	ALD Simulations	Ch. 3, pp. 47-69	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Hwang, Cheol Seong; Kim, Seong Keun; Lee, Sang Woon	Mass-Production Memories (DRAM and Flash)	Ch. 4, pp. 73-122	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Raoux, Simone; Ritala, Mikko	PCRAM	Ch. 5, pp. 123-148	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Hoffman-Eifert, Susanne; Watanabe, Takayuki	FeRAM	Ch. 6, pp. 149-171	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9

Han, Jeong Hwan; Cho, Moonju; Delabie, Annelies; Park, Tae Joo; Hwang, Cheol Seong	Front End of the Line Process	Ch. 7, pp. 175-208	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Kim, Hyungjun; Kim, Soo-Hyun; Lee, Han-Bo-Ram	Back End of Line	Ch. 8, pp. 209-238	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Chu, Schbuert	ALD Machines	Ch. 9, pp. 241-255	Atomic Layer Deposition for Semiconductors	Hwang, Cheol Seong	Springer New York	2014	https://link.springer.com/book/10.1007/978-1-4614-8054-9
Zhang, H.	Nanostructures Development with Atomic Layer Deposition	Ch. 6, pp. 123-140	Advanced Nano Deposition Methods	Lin, Y.; Chen, X.	Chemical Industry Press	2016	https://dx.doi.org/10.1002/9783527696406
Ramachandran, Ranjith K; Detavernier, Christophe; Dendooven, Jolien	Atomic Layer Deposition for Catalysis	Ch. 14, pp. 335-358	Nanotechnology in Catalysis	van de Voorde, M.; Sels, B.	Wiley-VCH	2017	https://doi.org/10.1002/9783527699827.ch14
Dendooven, Jolien; Detavernier, Christophe	Basics of Atomic Layer Deposition: Growth Characteristics and Conformality	Ch. 1, pp. 1-40	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch1
Macco, Bart; van de Loo, Bas W. H.; Kessels, Wilhelmus M. M.	Atomic Layer Deposition for High-Efficiency Crystalline Silicon Solar Cells	Ch. 2, pp. 41-99	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch2
Martinson, Alex	ALD for Light Absorption	Ch. 3, pp. 101-118	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch3
Guerra-Nunez, Carlos; Park, Hyung Gyu; Utke, Ivo	Atomic Layer Deposition for Surface and Interface Engineering in Nanostructured Photovoltaic Devices	Ch. 4, pp. 119-148	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch4
Liu, Lifeng	Atomic Layer Deposition of Electrocatalysts for Use in Fuel Cells and Electrolyzers	Ch. 5, pp. 149-181	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch5
Nilsen, Ola; Gandrud, Knut B.; Amund, Ruud; Fjellvåg, Helmer	Atomic Layer Deposition for Thin-Film Lithium-Ion Batteries	Ch. 6, pp. 183-207	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch6
Cassir, Michel; Melendez-Ceballos, Arturo; Chavanne, Marie-Helene; Dallel, Dorra; Ringuede, Armelle	ALD-Processed Oxides for High-Temperature Fuel Cells	Ch. 7, pp. 209-221	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch7
Santinacci, Lionel	ALD for Photoelectrochemical Water Splitting	Ch. 8, pp. 225-257	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch8
Karppinen, Maarit; Karttunen, Antti J.	Atomic Layer Deposition of Thermoelectric Materials	Ch. 9., pp. 259-274	Atomic Layer Deposition in Energy Conversion Applications	Bachmann, Julien	Wiley-VCH	2017	https://onlinelibrary.wiley.com/doi/10.1002/9783527694822.ch9
Muneshwar, Triratna; Miao, Mengmeng; Boryjeny, Elham; Cadien, Ken	Atomic layer deposition: Fundamentals, practice, and challenges	Ch. 11, pp. 359-377	Handbook of Thin Film Deposition (4th ed)	Seshan, Krishna; Schepis, Dominic	William Andrew	2018	http://dx.doi.org/10.1016/B978-0-12-812311-9.00011-6
Ghazaryan, Lilit; Pfeiffer, Kristin; Schmitt, Paul; Beladiya, Vivek; Kund, Stefan; Szeghalmi, Adriana	Atomic Layer Deposition		Digital encyclopedia of applied physics		Wiley-VCH	2020	https://dx.doi.org/10.1002/3527600434.eap813
Liu, Hongfei; Mahata, Chandreswar	Metal oxides and metal thin films by atomic layer deposition (ALD), liquid-ALD, and succ	Ch. 7, pp. 153-182	Energy Saving Coating Materials		Elsevier	2020	http://dx.doi.org/10.1016/B978-0-12-822103-7/00007-8
Akbari, Mohammad Karbalaei; Zhuiykov, Serge	Atomic Layer Deposition of Two-Dimensional Semiconductors	Ch. 2, 36 pp.	Ultrathin Two-Dimensional Semiconductors for Novel Electronic Applications		CRC Press	2020	https://doi.org/10.1201/9780429316784
van Ommen, Ruud; Goulas, Aristeidis; Puurunen, Riikka	Atomic Layer Deposition		Kirk-Othmer Encyclopedia of Chemical Technology		John Wiley and Sons	2021	https://dx.doi.org/10.1002/0471238961.koe00059
Barry, Sean; Gordon, Peter; Vandalon, Vincent	Common Precursors and Surface Mechanisms for Atomic Layer Deposition	In press (as of 18 April 2022)	Comprehensive Organometallic Chemistry IV	Parkin, G.; Meyer, K.; O'Hare, D.	Elsevier	2022	https://doi.org/10.1016/B978-0-12-820206-7.00117-7
Barry, Sean	Chemistry of Atomic Layer Deposition	pp. 1-105 (whole book)	Chemistry of Atomic Layer Deposition		de Gruyter	2022	https://doi.org/10.1515/9783110712537